

Title (en)
POLISHING PAD

Title (de)
POLIERKISSEN

Title (fr)
TAMPON DE POLISSAGE

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Application
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Abstract (en)
[origin: WO2009025748A1] The invention provides a polishing pad comprising a polishing layer having a polishing surface comprising plurality of grooves disposed into the polishing layer a measurable depth from the polishing surface, and a barrier region free of grooves, and a transparent window disposed in and surrounded by the barrier region.

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JP 2006239833 A 20060914 - NITTA HAAS INC

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